

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :

HARADA et al.

Group Art Unit: TBA

Serial No.: TBA

Examiner: TBA

Filed: Herewith

For: POLYMERS, RESIST COMPOSITIONS AND PATTERNING PROCESS

4/A
D.G.
6-19-02PRELIMINARY AMENDMENTAssistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend the claims as follows:

- AI
5. (Amended) A chemically amplified, positive resist composition comprising
- (A) the polymer of claim 1
 - (B) an organic solvent, and
 - (C) a photoacid generator.